

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 02-253620

(43)Date of publication of application : 12.10.1990

(51)Int.Cl.

H01L 21/304

(21)Application number : 01-073787

(71)Applicant : OKI ELECTRIC IND CO LTD

(22)Date of filing : 28.03.1989

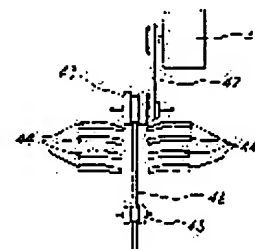
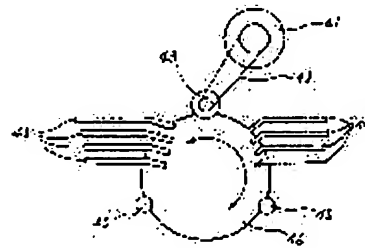
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(54) WASHING DEVICE FOR SEMICONDUCTOR SUBSTRATE

(57)Abstract:

PURPOSE: To enable fine foreign objects, dust, etc., to be removed efficiently by rotary-driving a semiconductor substrate in both left and right directions and by spraying a fluid or a gas matching to the rotation onto the front and rear surfaces of the semiconductor substrate.

CONSTITUTION: A semiconductor substrate 46 is supported by a rotary-drive pulley 43 and two supporting guide pulleys 42, rotation of a motor for rotary-driving wafer 41 is transmitted to the rotary-drive pulley 43 by the drive belt 42, thus enabling the semiconductor substrate 46 to rotate at high speed. Then, each fluid is sprayed out of a pressurized water, a chemical solution, and an inactive gas jet-out port 44 and is sprayed over the semiconductor substrate 46. Thus, the semiconductor substrate 46 is fitted vertically and the front and rear surfaces of the substrate 46 are washed simultaneously while being rotated so that the rear surface can be washed simultaneously. Also, foreign objects, dust, etc., separated from the semiconductor substrate 46 by the fluid drop effectively and do not remain on the surface of the semiconductor substrate.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]